

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Application Serial No. 10/050,334
Filing Date January 15, 2002
Inventor Vishnu K. Agarwal et al.
Assignee Micron Technology, Inc.
Group Art Unit 2813
Examiner Yennhu B Huynh
Attorney's Docket No. MI22-1913
Title: Capacitor Fabrication Methods and Capacitor Constructions and
Enhanced Surface

SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT

References – See Attached Form PTO-1449


In compliance with 37 C.F.R. §§ 1.56, 1.97 and 1.98, your attention is directed to the United States patents and other references listed on the attached Form PTO-1449. No admission is made regarding whether all the submitted references are prior art.

Citation of these references is respectfully requested.

Respectfully submitted,

Dated: 11 Jul 2005

By: _____


James E. Lake
Reg. No. 44,854

07/14/2005 WABDELRI 00000064 10050334

01 FC:1806 180.00 OP

EV550718036

Form PTO-1449		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO. MI22-1913		SERIAL NO. 10/050,334		
<div style="border: 1px solid black; border-radius: 50%; padding: 10px; display: inline-block;"> OFFICE JUL 11 2005 PATENT & TRADEMARK OFFICE </div> LIST OF ART CITED BY APPLICANT <small>(Use several sheets if necessary)</small>				APPLICANT: Vishnu K. Agarwal et al.				
				FILING DATE January 15, 2002		GROUP 2813		
U.S. PATENT DOCUMENTS								
*Examiner's Initials	AA	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate	
	AA	6,359,295 B2	03/2002	Yang et al.				
	AB	6,403,156	06/2002	Jang				
	AC	6,596,602 B2	07/2003	Lizuka et al.				
	AD	6,627,462 B1	09/2003	Yang et al.				
	AE	6,664,186 B1	12/2003	Callegari et al.				
	AF	6,746,930	06/2004	Yang				
	AG							
	AH	2002/0142488	10/2002	Hong, Suk-Kyoung				
	AI	2002/0109198 A1	08/2002	Yang et al.				
FOREIGN PATENT DOCUMENTS								
		Document Number	Date	Country	Class	Subclass	Translation	
							Yes	No
	AJ	KR 2002046433	05/2003	Lee, J.W.				
	AK	EP 1 508 906 A2	02/2005	Lee et al.				
	AL							
OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)								
	AM		Ritala et al.; <i>Perfectly Conformal TiN and Al2O3 Films Deposited by Atomic Layer Deposition</i> ; Chemical Vapor Deposition, v. 5, No. 1, 1999, pp. 7-9.					
	AN							
	AO							
EXAMINER		DATE CONSIDERED						
<small>*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.</small>								